

Design and Characterization of a Radiation-Hardened CMOS Image Sensor Prototype

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Outline

- **Introduction**
- **Radiation Effects**
- **Radiation-Hardened-By-Design (RHBD)**
- **Prototype Specifications and Designs**
- **Measurement Results**
- **Summary & Outlook**

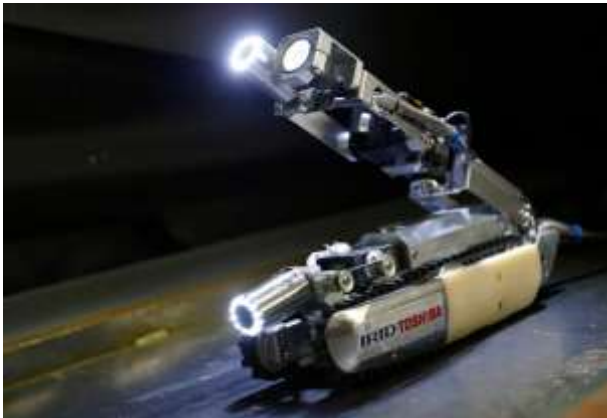
Introduction

Applications Radiation-tolerant cameras are demanding for imaging and monitoring Systems.

Nuclear Reactor



Remote Control



Space Exploration



HEP Experiments

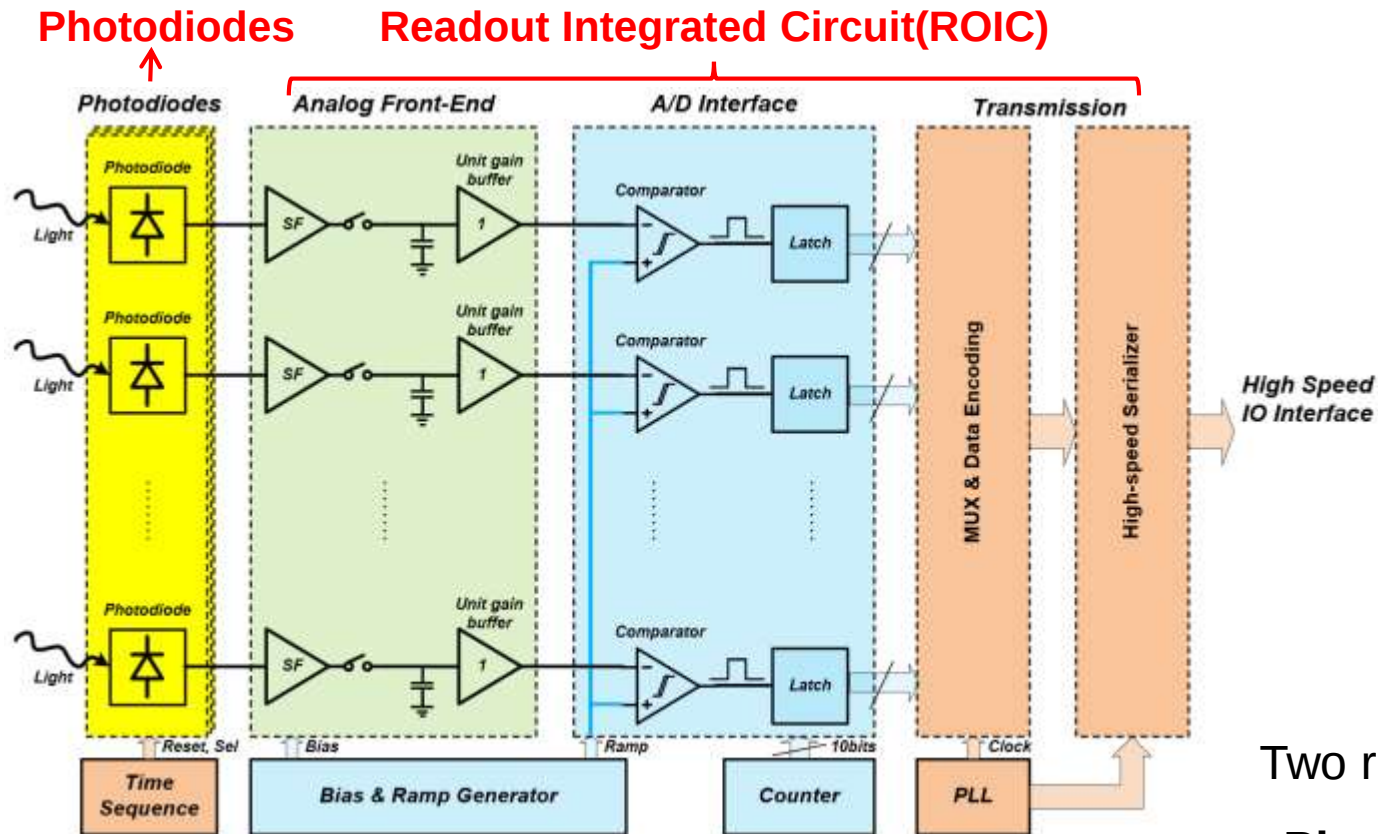


Current States Three common radiation hardening approaches are as below.

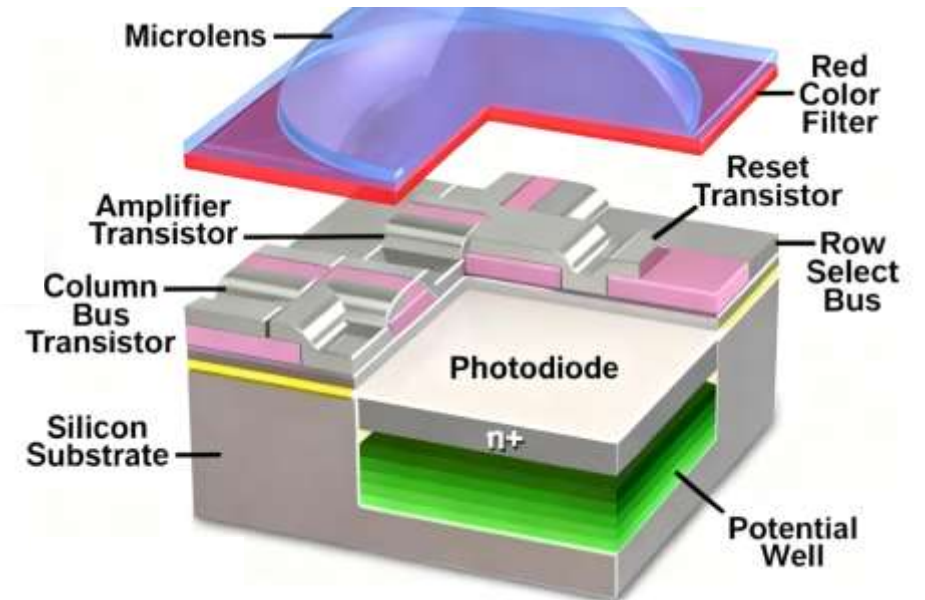
<i>Conditions & Parameters</i>	<i>Approach-A</i> 😞	<i>Approach-B</i> 😊	<i>Approach-C</i> 😊
Shielding with Lead ?	YES	NO	YES
Radiation Tolerant Sensor ?	NO	YES	YES
Weight	Very Heavy (~20kg) 😞	Light (<5kg) 😊	Not Heavy (5-10kg)
Radiation Tolerance	Low 😞	High 😊	Even Higher 😊
Lifetime	Short 😞	Long 😊	Long 😊

Introduction

CMOS Image Sensor



Block diagram of the CMOS Image Sensor



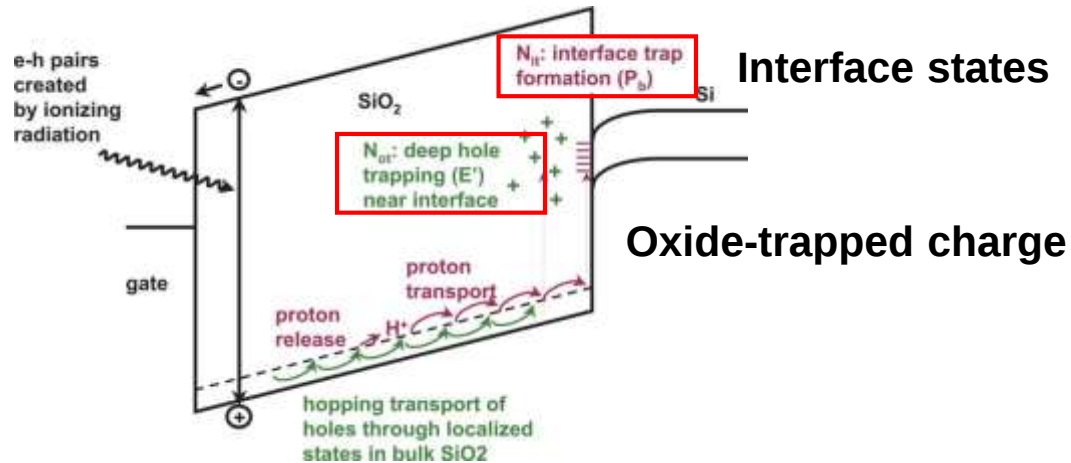
Two radiation-vulnerable critical blocks:

- **Photodiode:** Incident light converted into charge signals
- **ROIC:** transistors for amplification, digitization ...

Radiation Effects on the Image Sensor

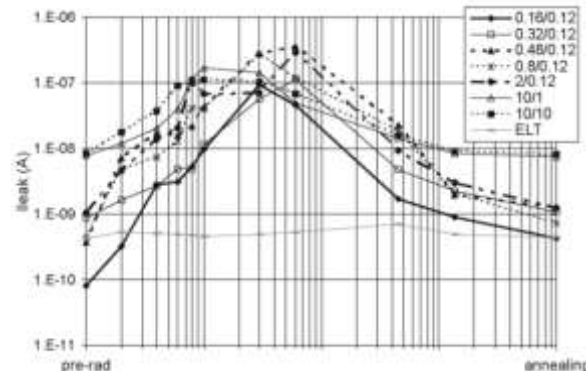
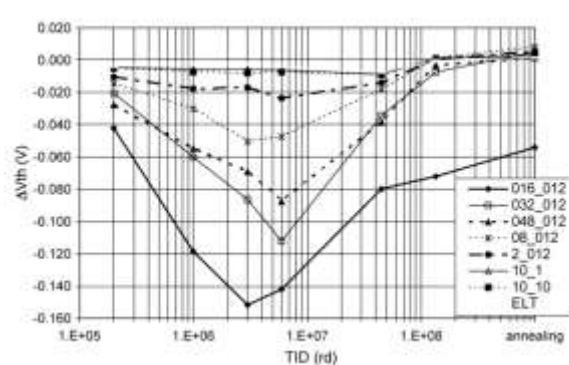
Total Ionizing Dose (TID) Effect on Photodiodes and Transistors

Ref: James R. Schwank, et al. *Radiation Effects in MOS Oxides*.

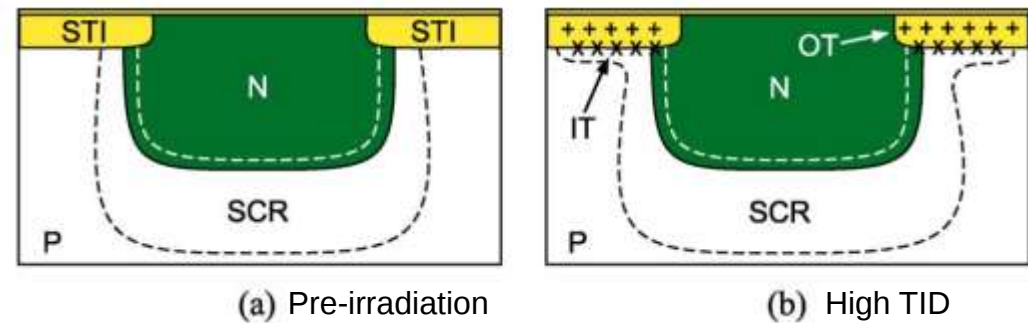


Ref: Federico Faccio and Giovanni Cervelli.

Radiation-Induced Edge Effects in Deep Submicron CMOS Transistors.



Ref: V. Goiffon, et al. *Generic Radiation Hardened Photodiode Layouts for Deep Submicron CMOS Image Sensor Processes.*



For photodiodes:

Dark current increase, Depletion region extension

For transistors:

Threshold voltage shift, Leakage current increase

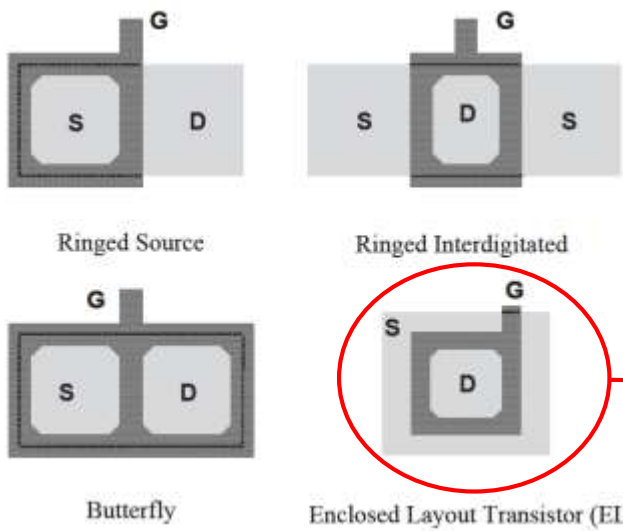
Summary

- STI is a big trouble for both photodiodes and transistors
- What about gate oxide?

Radiation-Hardened-By-Design (RHBD)

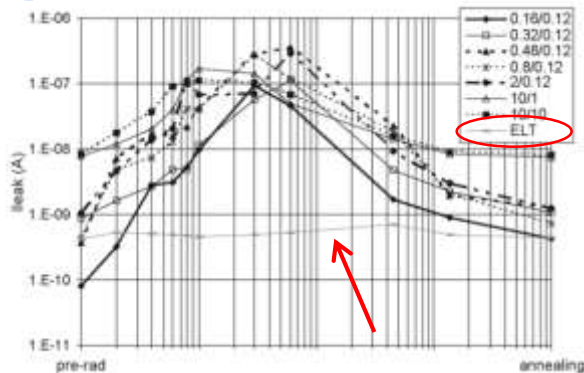
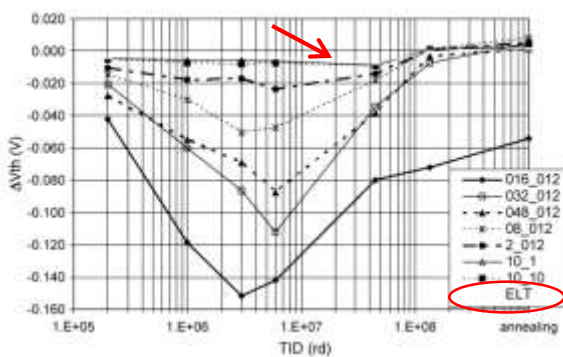
Total Ionizing Dose (TID) Effect

Ref: *Radiation Effects on Embedded Systems.*



Ref: *Federico Faccio and Giovanni Cervelli.*

Radiation-Induced Edge Effects in Deep Submicron CMOS Transistors.



Layout techniques to enhance the radiation tolerance of MOS transistors

- ▶ mitigate the TID effect on STI
- ▶ but can not totally eliminate the TID effect on gate oxide
- ▶ ELT is very tolerant to ionizing radiation ($\sim 100\text{Mrad}$)
- ▶ Gate oxide is much more tolerant to ionizing radiation

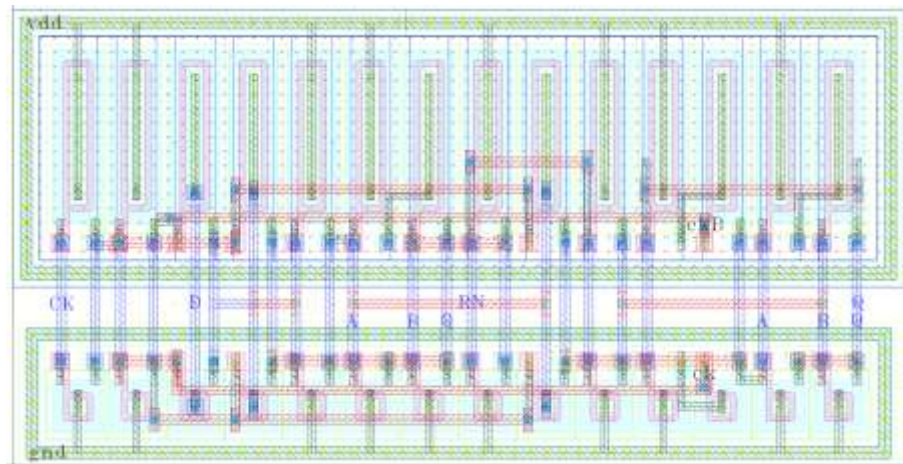
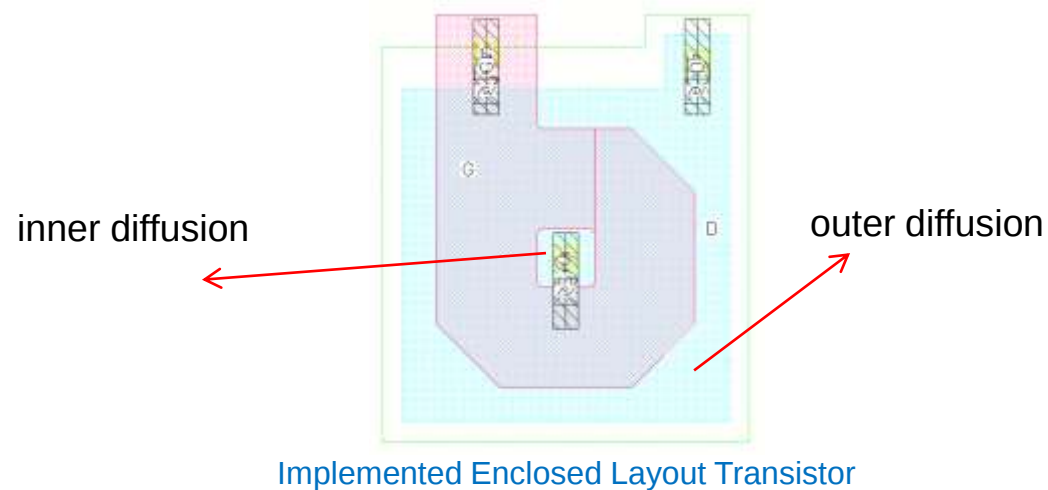
Radiation-Hardening Strategy

Comparison of STI oxide and gate oxide

180nm process	STI	Gate Oxide
depth / nm	~ 400	~ 4

Prototype Designs

Read Out Integrated Circuit (ROIC)



D Flip-Flop Layout with ELT

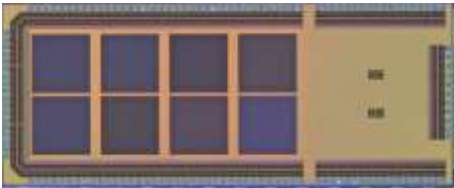
*For radiation-hardened **photodiodes**, please follow the presentation of [J. Deng](#) on Tuesday morning.*

- ▶ All analog circuits (and critical digital circuits) designed with enclosed layout transistors.
- ▶ P+ and N+ guardrings implemented to decrease latch-up possibility.
- ▶ Outer diffusion of adjacent NMOS transistors connected to the same node or isolated by P+ rings to cut the leakage path between transistors.

Prototype Specifications

Timeline of the Image Sensor

MPW1: To study the RHBD strategy.



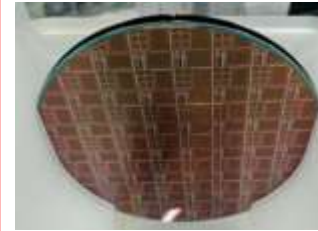
Features:

- 64×64 Pixel Array
- RH / STD Photodiodes
- RH / STD ADC

Today's topic!

Sensor Prototype I

To characterize TID performance



Features:

- 1280×720 Pixel Array
- 1 Gbps data rate
- 100Mrad-level radiation tolerance

Camera Prototype I

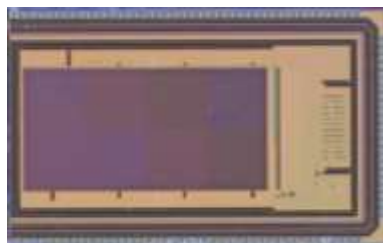
Camera Prototype II

Sensor Prototype II

—— higher performance

- Photodiode optimization (geometry ...)
- ROIC performance improvement (power, noise ...)
- Triple modular redundancy (Single Event Effect)

MPW2: To validate the read out chain.

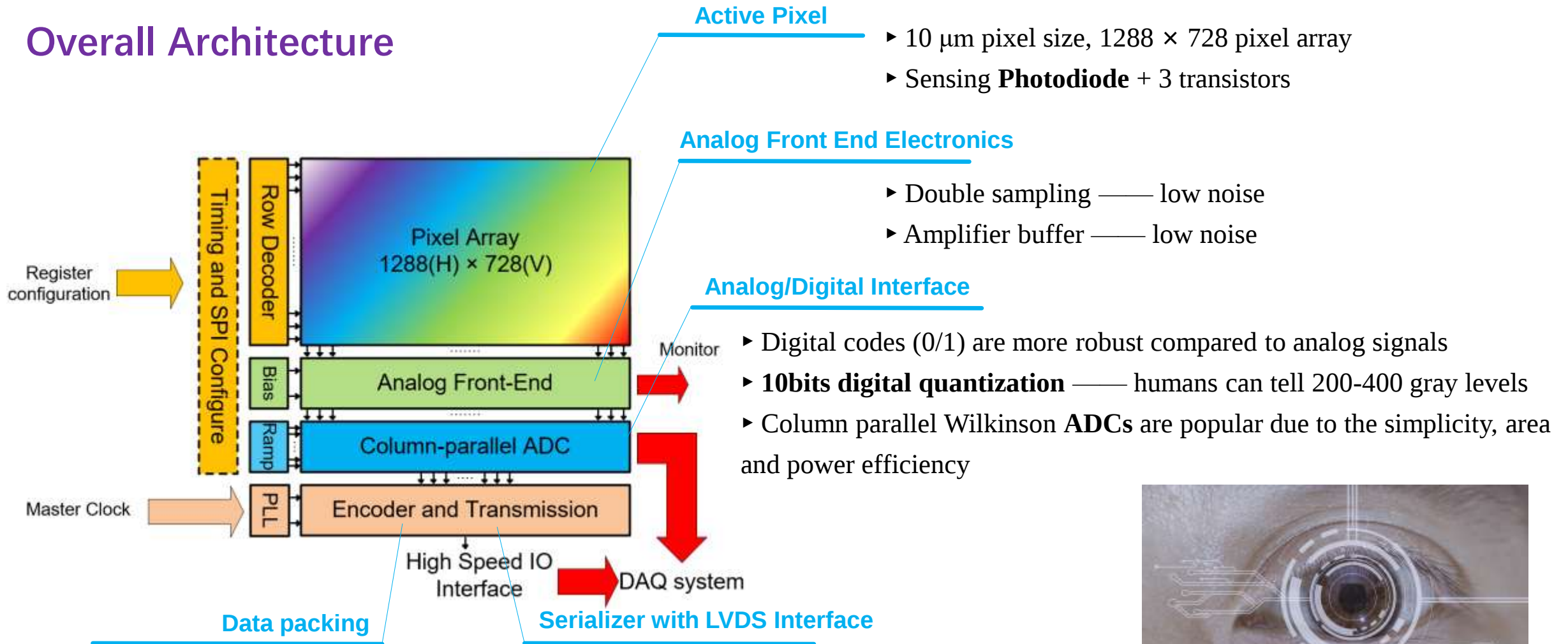


Features:

- 256×128 Pixel Array
- Column-parallel ADC
- LVDS interface

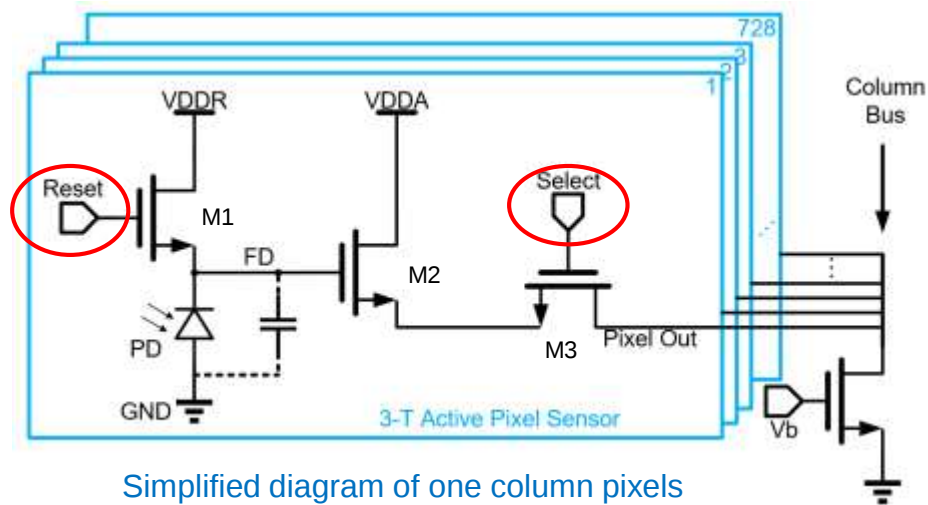
Prototype Specifications

Overall Architecture

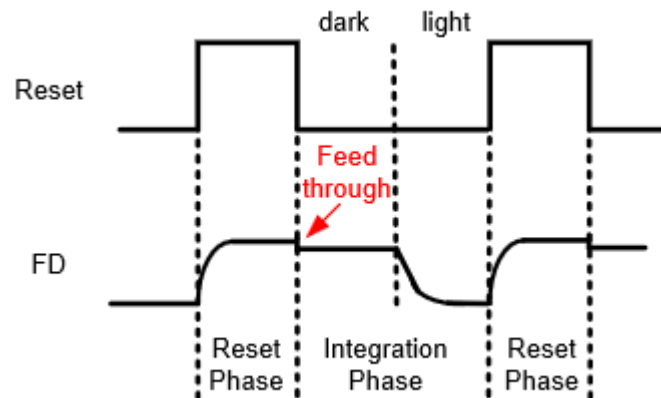


Prototype Designs

In-pixel Electronics



Simplified diagram of one column pixels



Working principle of the pixel

►3-T Active Pixel Sensor

Photodiode + 3 transistors in $10 \times 10 \mu\text{m}^2$

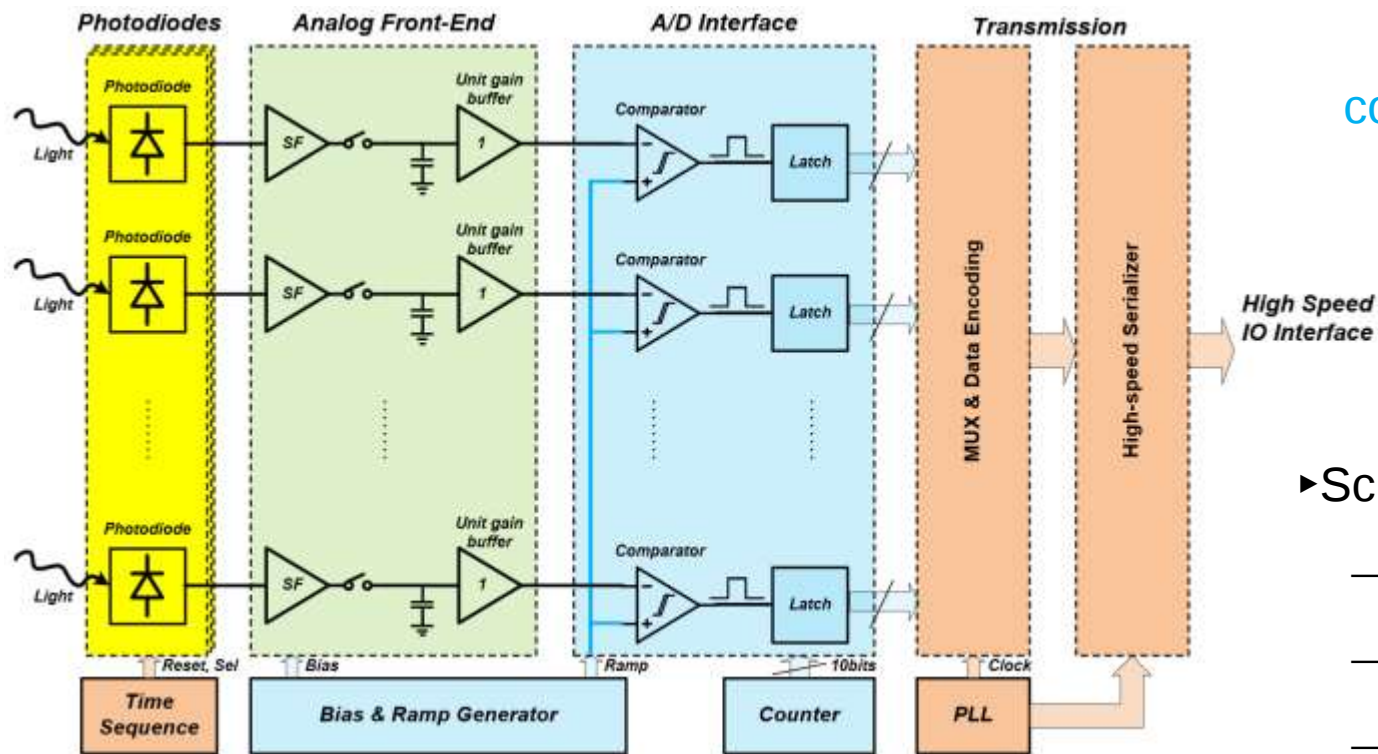
M1 and M3 work as switches, M2 is used to drive the large load capacitance of the column bus

►In reset phase, the reset transistor is on to **charge** the photodiode to a high level (reset level).

►In integration phase, the reset transistor is off and photodiode **discharges** due to leakage current or photon-generated electron-hole pairs.

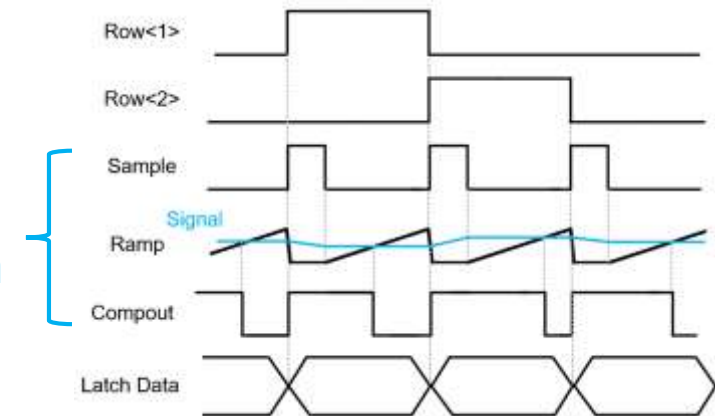
Prototype Designs

Read Out Scheme



Block diagram of the readout chain

A/D
conversion



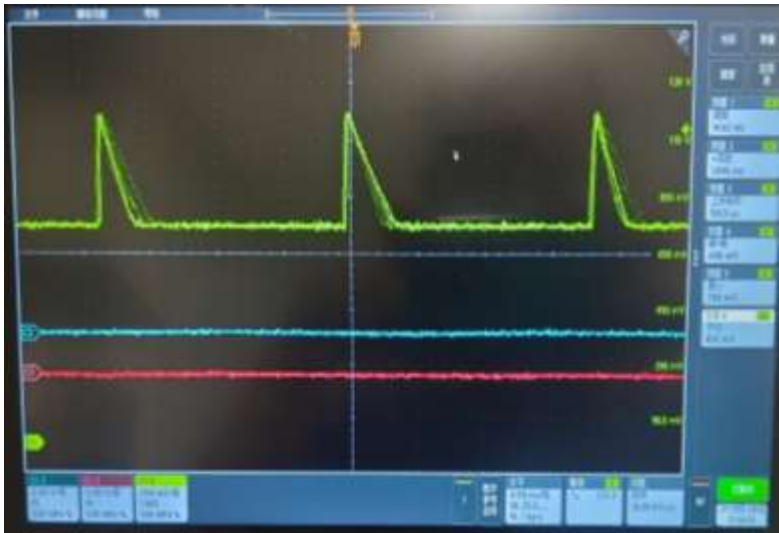
Time Sequence of readout scheme

►Scheme:

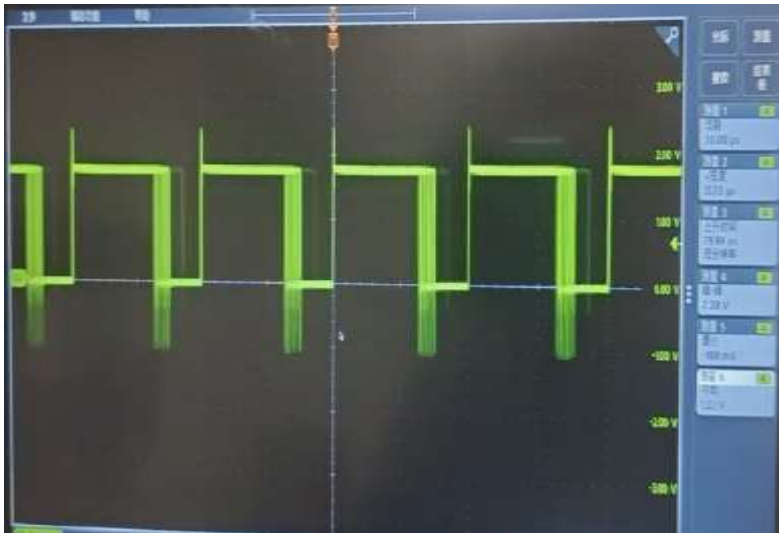
- photodiodes for photon-electron conversion
- pixels readout row by row
- voltages sampled and digitized
- digitized outputs formatted and transmitted

Measurements Results

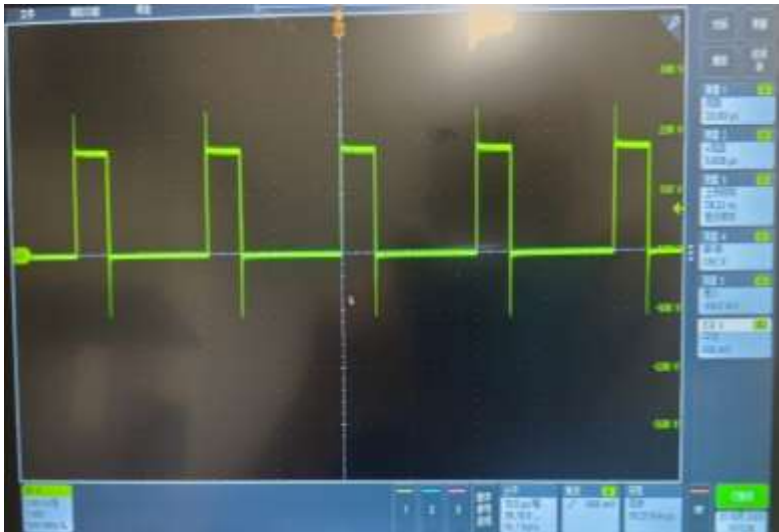
Functionalities



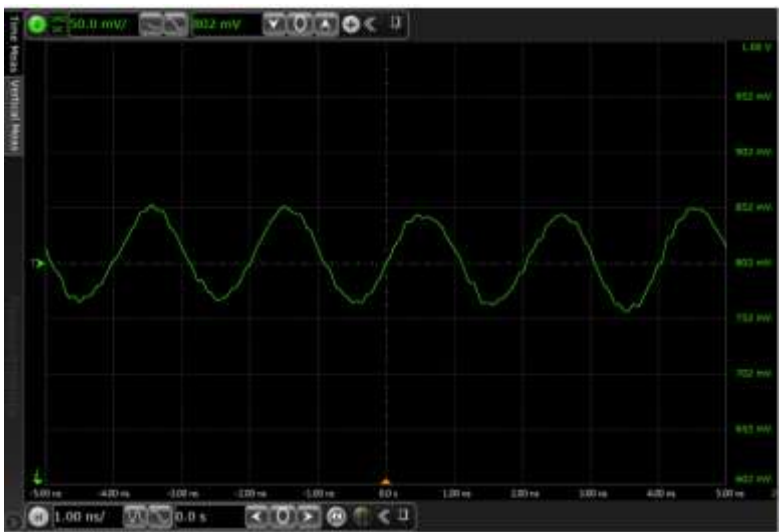
Pixel



Comparator
Out



Sample

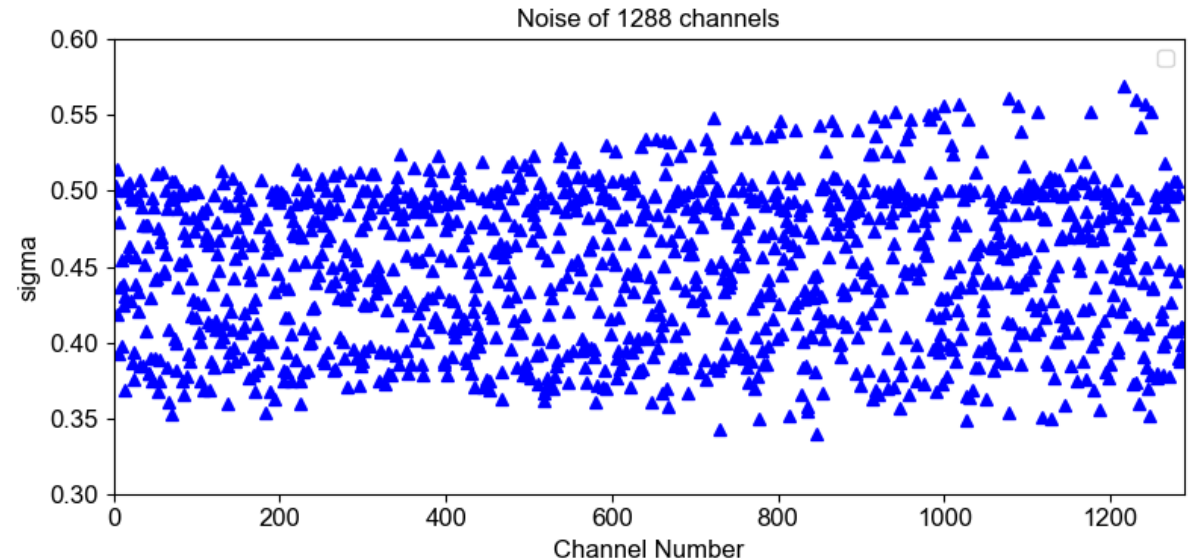
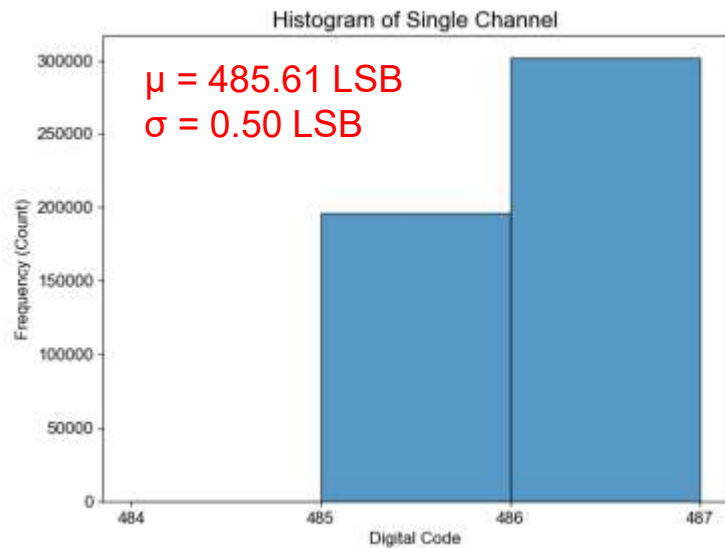


PLL
500 MHz

Measurements Results

A/D Conversion — Noise

Methods: Study digital outputs distribution with a fixed input voltage



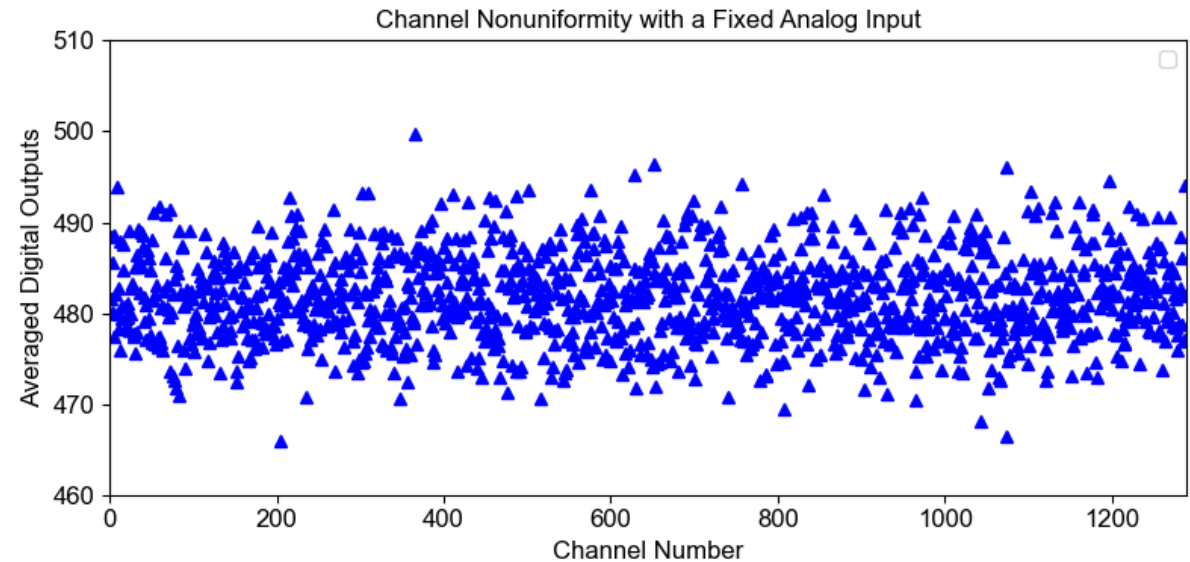
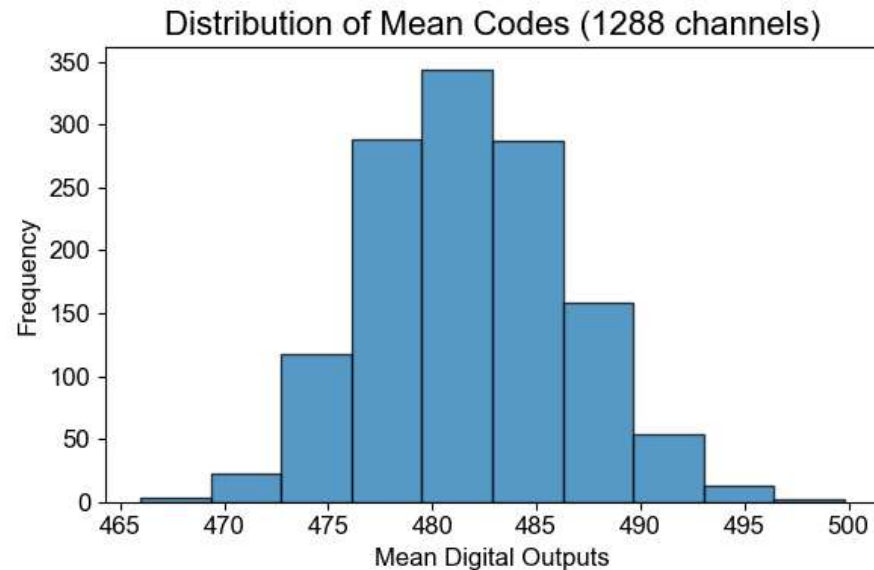
- ▶ **Only 3** digital codes obtained
- ▶ Noise of ADC calculated to be 0.50 LSB

- ▶ Uniform Noise behaviors of 1288-channel ADCs
- ▶ Acceptable conversion noise for the image sensor

Measurements Results

A/D Conversion — Column Offset Correction

- Methods:
1. Measure (1288) mean digital values with a fixed input voltage
 2. Calibrate DC offset of 1288 ADCs to get good uniformity



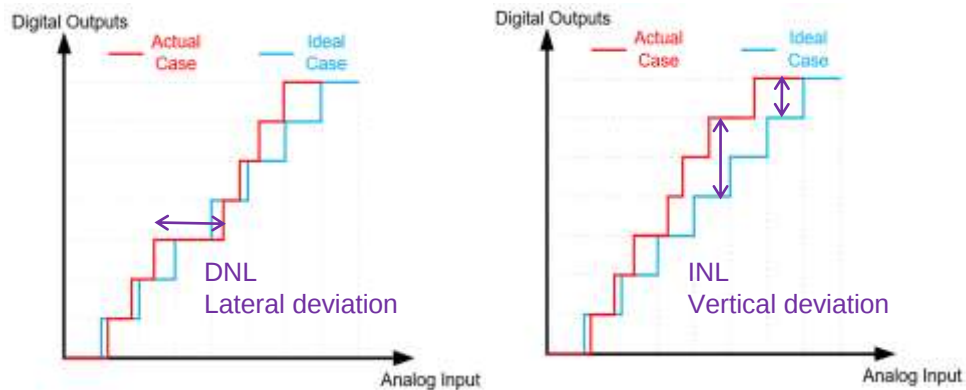
- ▶ The results indicate the Monte Carlo nonuniformity of column-level ADCs.
- ▶ From the distribution, the DC offset can be corrected with a digital algorithm

Measurements Results

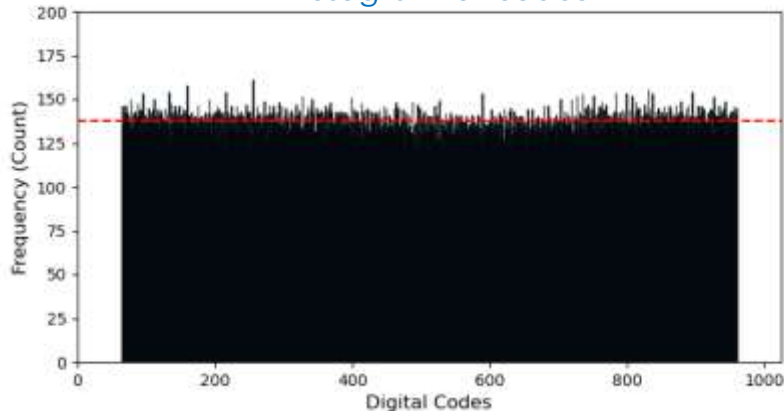
A/D Conversion — Histogram and Nonlinearity

Methods: Measure digital outputs with a ramp wave for enough time
Calculate nonlinearity from digital codes histogram

Non-Linearity diagram



Histogram of codes



► Differential Non-Linearity (DNL)

DNL indicates the analog difference relative to the ideal situation

► Integral Non-Linearity (INL)

INL is the difference between the actual and the ideal digital output

► Histogram measurement

Ideally, the histogram distribution should be completely flat.

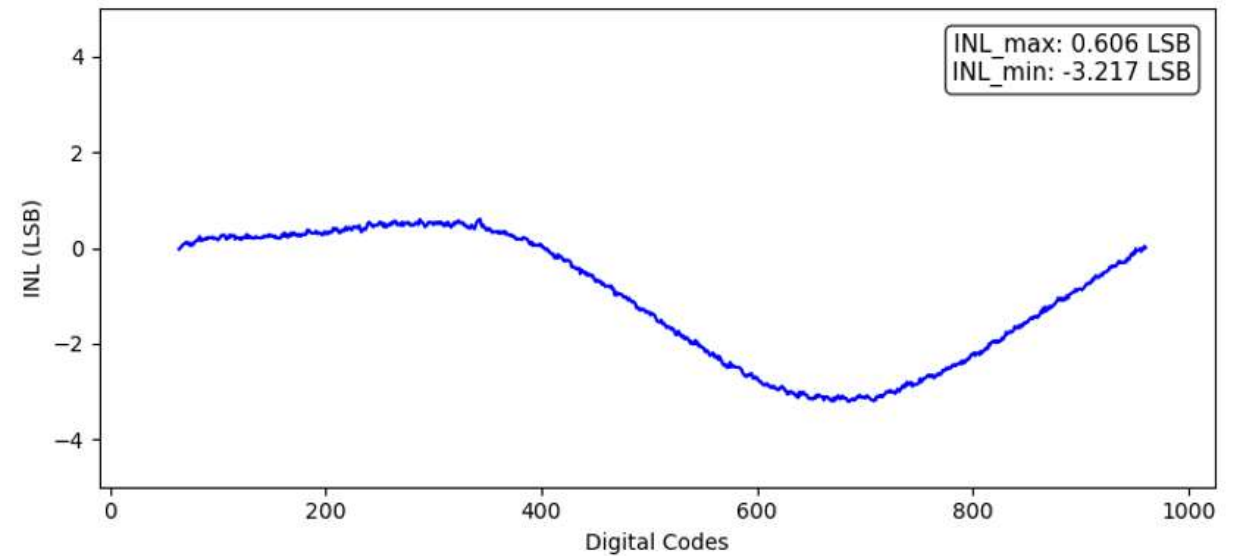
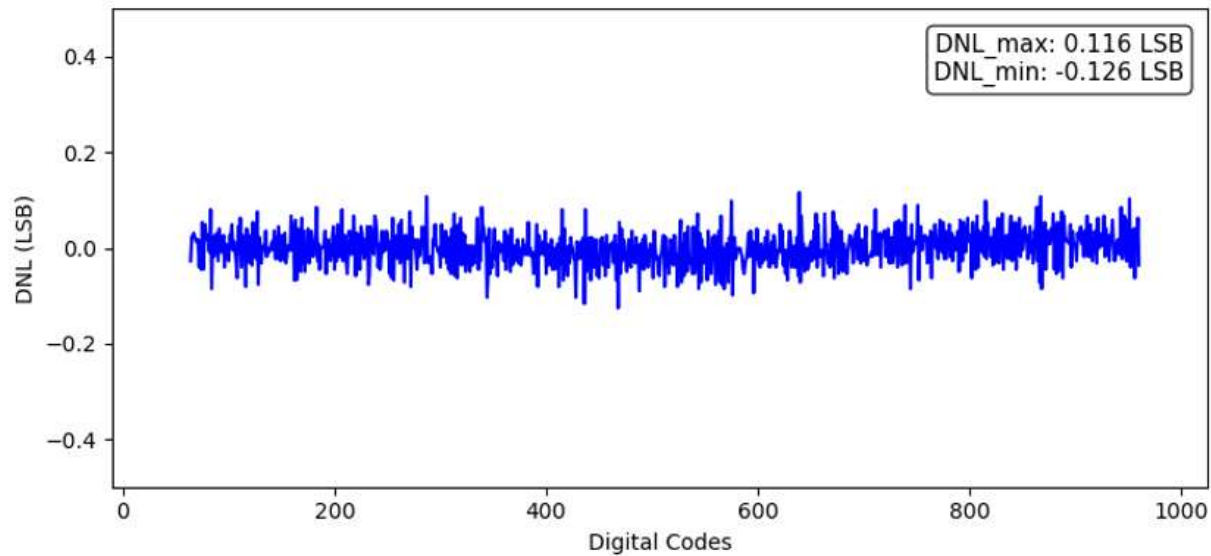
Actually, the histogram counts deviate from the average value.

$$DNL(n) = \frac{Counts_actual(n) - Counts_average}{Counts_average}$$

$$INL(n) = \sum_{i=0}^n DNL(i)$$

Measurements Results

A/D Conversion — Nonlinearity

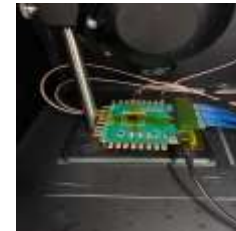


- ▶ The Differential Non-Linearity is relatively small and negligible
- ▶ The Integral Non-Linearity is a little high but it is acceptable for the imaging system

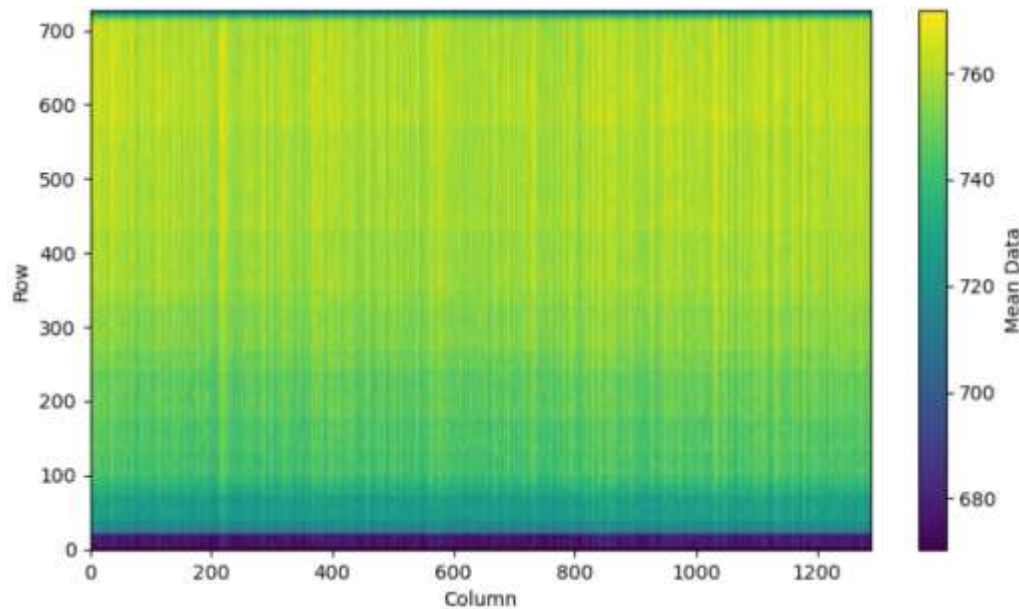
Measurements Results

Pixel Array — Dark Current

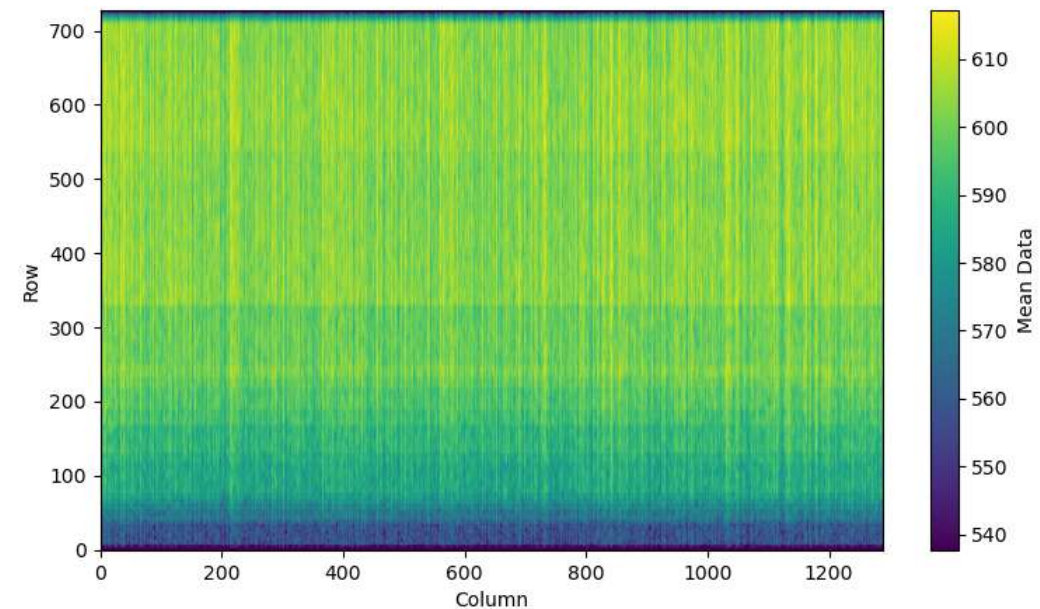
Under test!



Reset level of pixel matrix



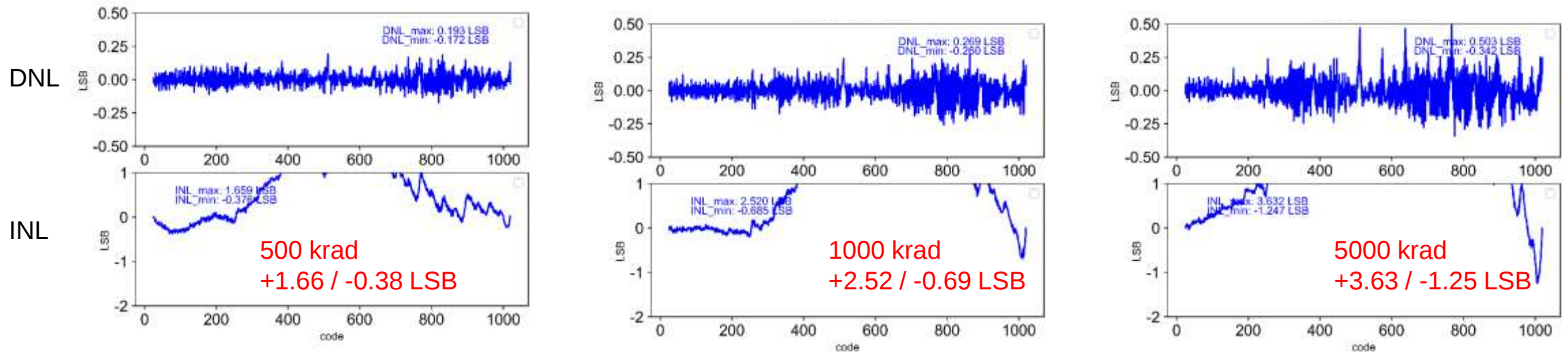
10ms dark current integration



- ▶ Strong non-uniformity in rows (0-20, 720-727) — matrix edge, but not fully understood
- ▶ Vertical stripes dominated by the column readout chain (can be calibrated)

Measurements Results

A/D Conversion — irradiation



- ▶ The results are from another ADC chip with similar design
- ▶ DNL rises from +0.20/-0.18 LSB → +0.50/-0.34 LSB
- ▶ INL changes from +1.66/-0.38 LSB → +3.63/-1.25 LSB

Summary & Outlook

Summary

- ▶ Pixel matrix information obtained with integrated read out chain
 - have to further understand the non-uniformity before imaging
- ▶ On-chip ADCs evaluated
 - DNL: **+ 0.12/-0.13 LSB**
 - INL: **+0.61/-3.21 LSB** (acceptable for the imaging system)
 - Noise: **0.45 LSB**
 - TID: deterioration of DNL and INL

Outlook

- ▶ Sensor characterization to be continued
- ▶ Irradiation (up to 100 Mrad) and annealing tests to be performed

Thanks!

Contribution List

J. Deng, X. Geng, P. Li, D. Liu, H. Zhu✉ (Zhejiang University)

T. Li, F. Yan, J. Liu, P. Yang (Central China Normal University)

Y. Cheng, Y. Qin, C. Feng (University of Science and Technology of China)

M. Ji, K. Li, S. Li, Y. Liu, Z. Luo, H. Pang, C. Wang, J. Wu, S. Xiao, L. Zhang, X. Li
(China Institute of Atomic Energy)

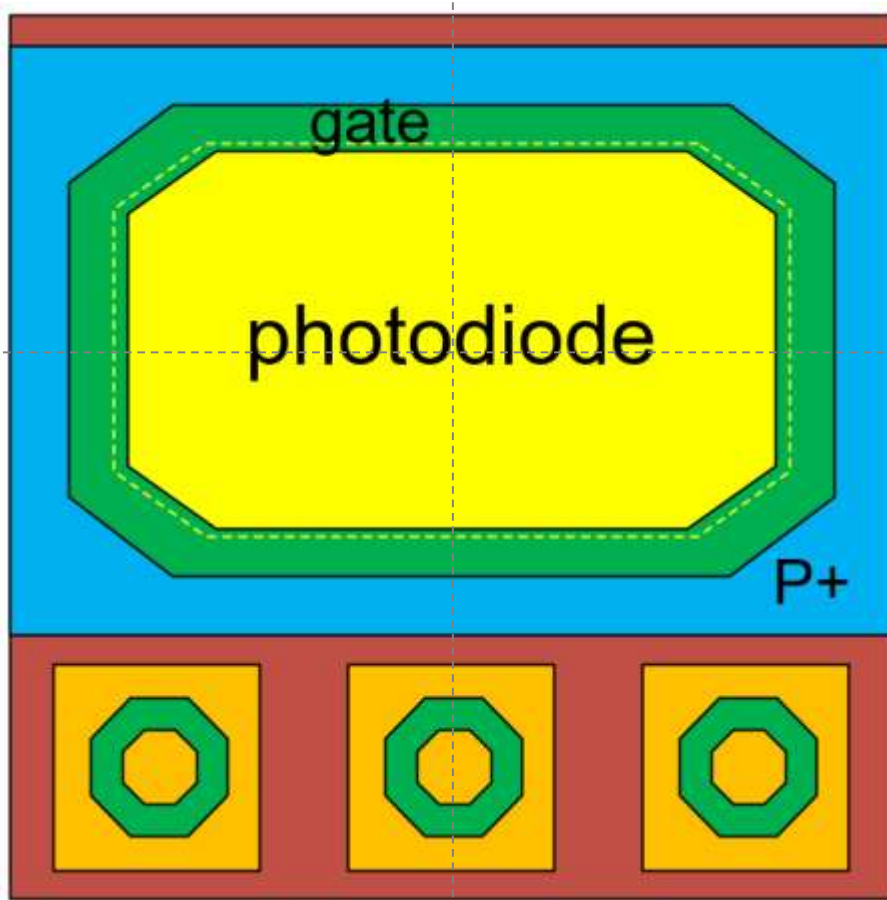


Thanks for your attention !

Backup

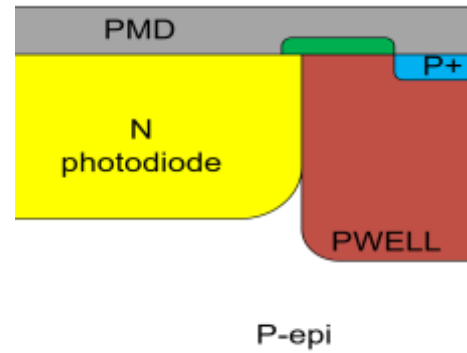
Backup

Photodiodes

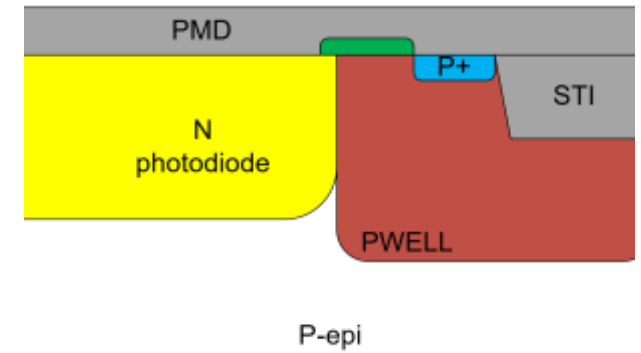


Simplified Pixel layout diagram
(Inspired by [V. Goiffon](#)(ISAE-SUPAERO Group))

Lateral cross section



Vertical cross section



- ▶ Gate Oxide replaces STI
- ▶ P+ to further prevent depletion region extension to STI
- ▶ In lateral case, pixels are isolated by P+ instead of STI
- ▶ In vertical case, pixels are isolated by P+ → STI → P+

For detailed information, please follow the presentation of [J. Deng](#) on Tuesday morning.

Backup

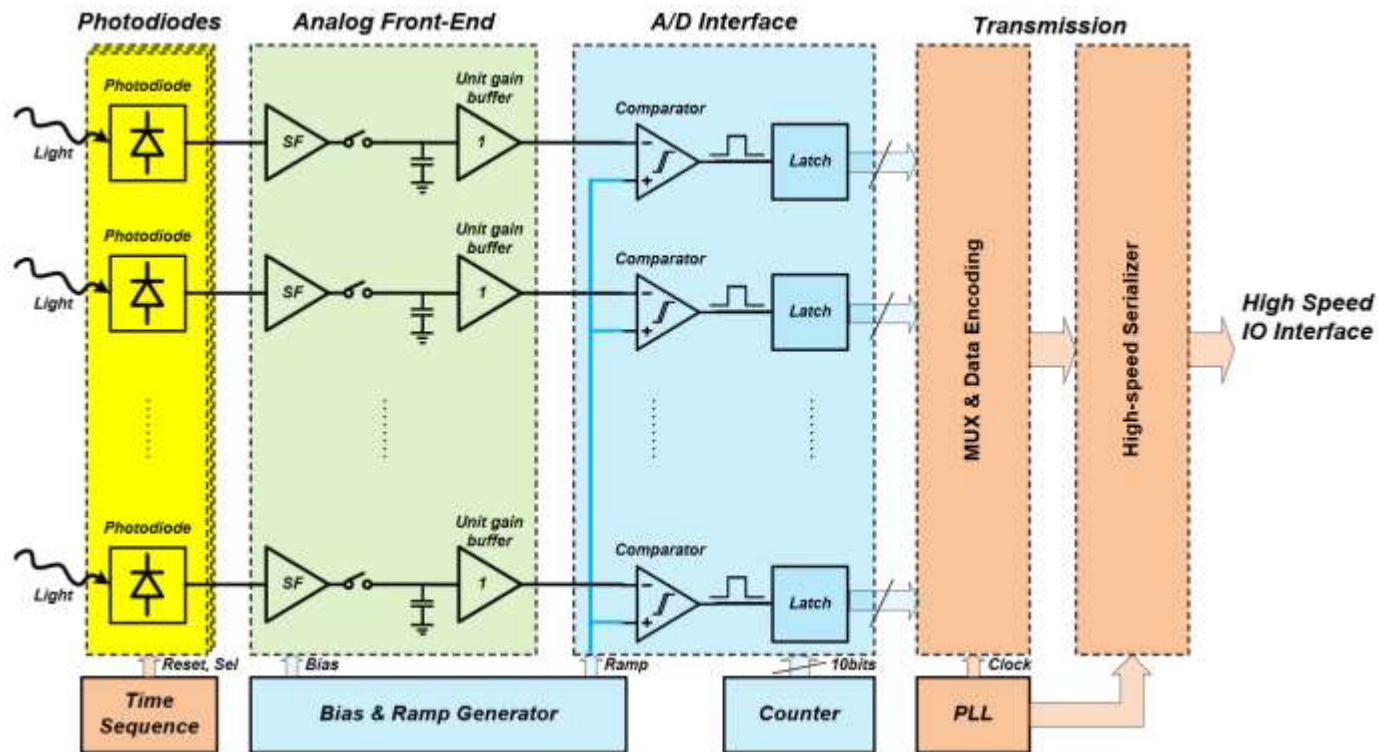
Aims and Requirements

Technology	180 nm CIS
Pixel Size	$10 \times 10 \mu\text{m}^2$
Number of Pixels	1280×720
Chip Dimensions	$14.7 \times 11.6 \text{ mm}^2$
Read Out Mode	Row-wise
Exposure Time	Tunable
Frame Rate	$> 60 \text{ FPS}$
ADC Resolution	$\geq 10 \text{ bits}$
Data Rate	$\geq 1 \text{ Gbps}$
Radiation Tolerance	$100 \text{ Mrad}(\text{SiO}_2)$ $10^{12} \text{ n}_{\text{eq}}/\text{cm}^2$

Backup

CMOS Image Sensor

Photodiodes Readout Integrated Circuit(ROIC)



Block diagram of the CMOS Image Sensor

► Photodiodes (Light Detection)

Convert incident light into charge signals

Each pixel includes reset & select control

► Analog Front-End (Signal Conditioning)

Source follower drive the load

Unity gain buffer escape coupling from ADC

► A/D Interface (Single-Slope Conversion)

Comparator detects crossing with ramp signal

Latch and counter generate digital outputs

► Bias & Ramp Generator

Provides bias current and reference ramp for ADCs

► Transmission (High-Speed Output)

Data encoding and multiplexing for multiple channels

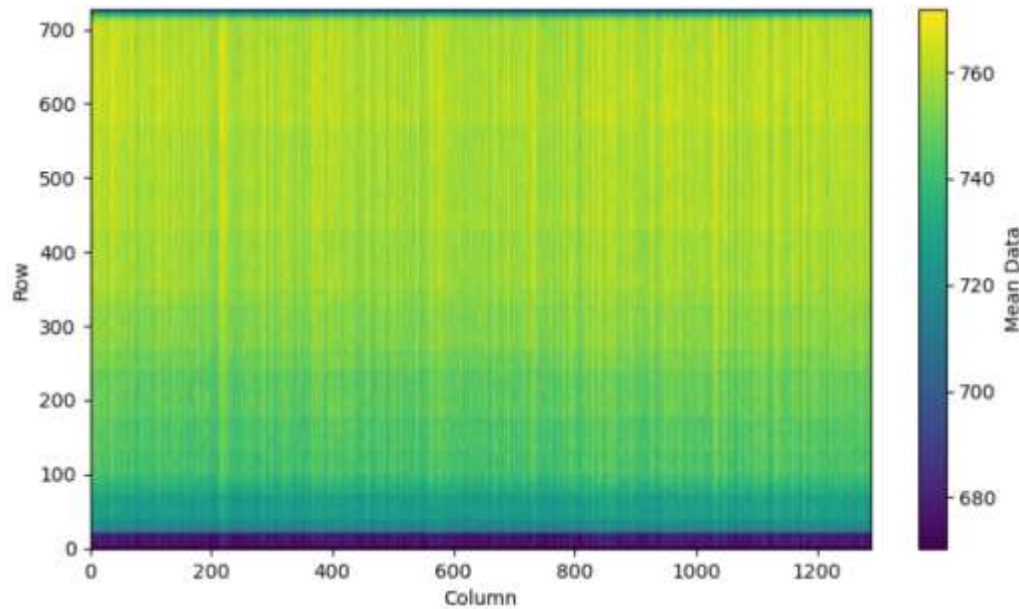
Serializer and PLL enable high-speed data interface

Backup

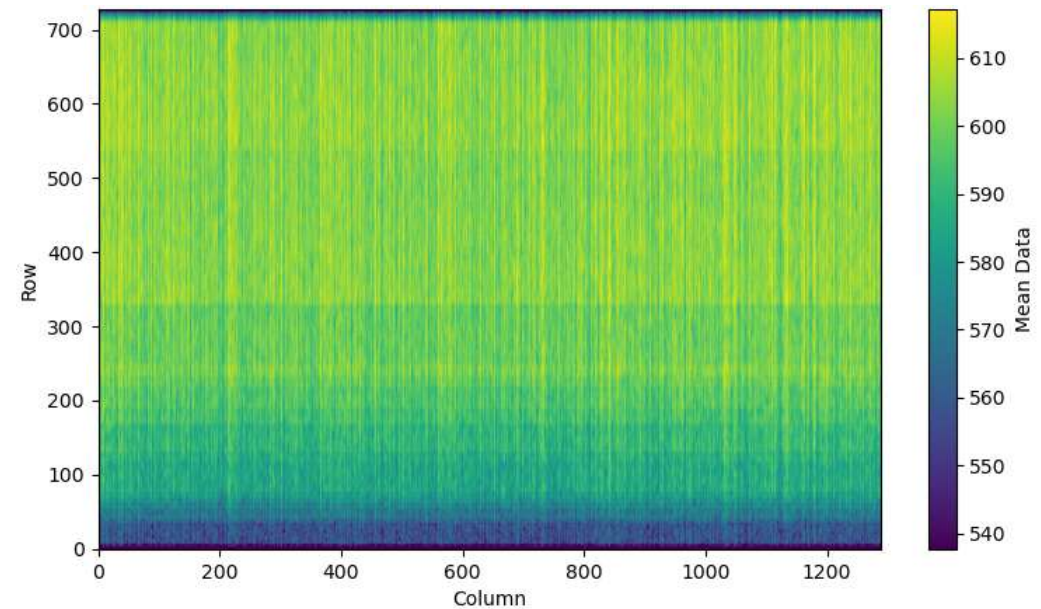
Pixel Array — Photon Incidents



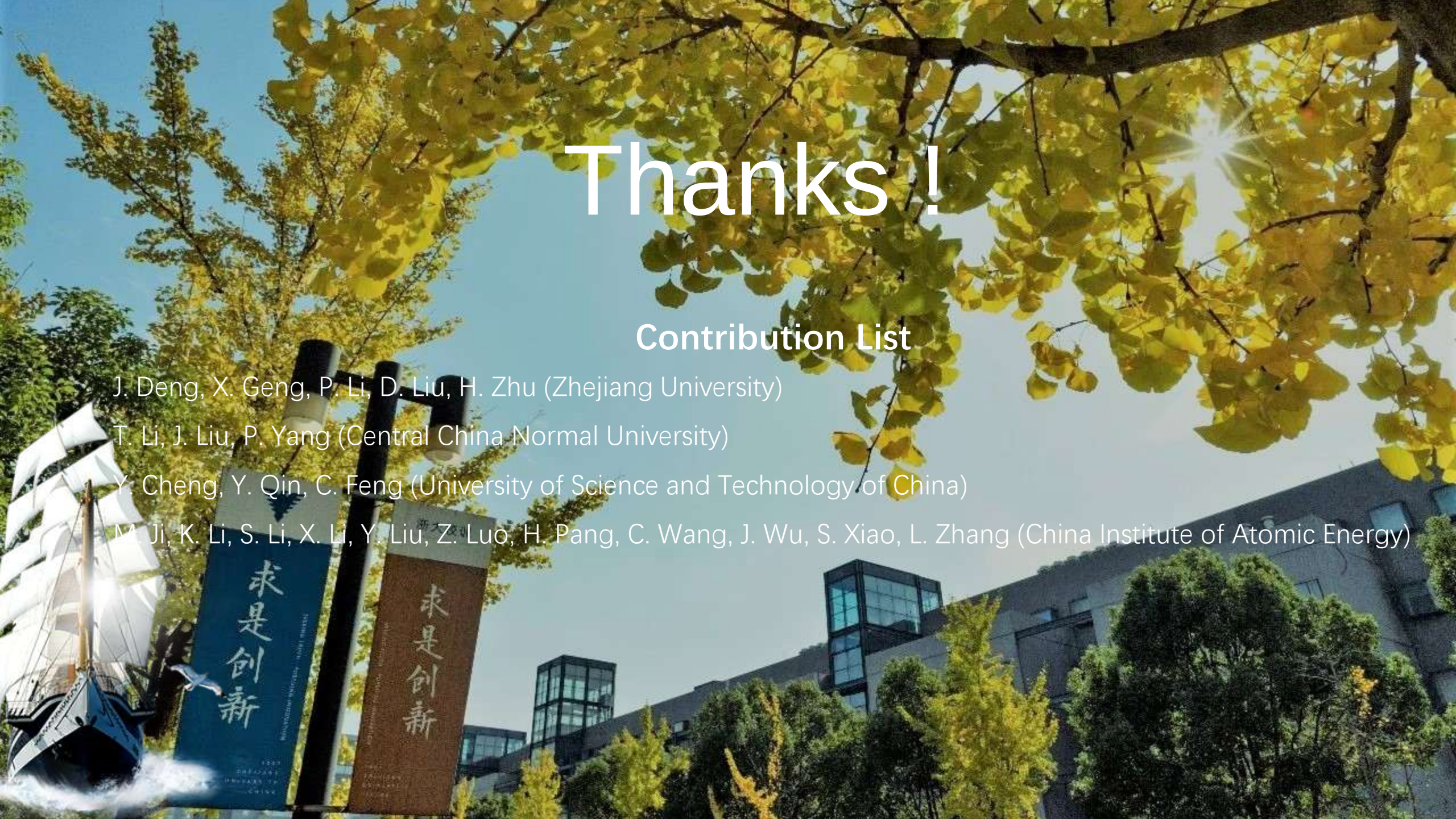
Reset level of pixel matrix



10ms photon incidents current integration



- Pictures obtained with a 520nm Light from Xenon lamp
- Overall behaviors are similar to the dark current case, but with higher current



Thanks !

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